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By 
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JFV

Attorney Docket No.: NECF 17.638A (100806-00232)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor: Mami MIYASAKA

Serial No.: 10/657,288

Confirmation No.: 1386

Filed: September 8, 2003

Title: **ELECTRON BEAM EXPOSURE MASK, ELECTRON BEAM
EXPOSURE METHOD, METHOD OF FABRICATING
SEMICONDUCTOR, AND ELECTRON BEAM EXPOSURE
APPARATUS**

Examiner: Saleha R. Mohamedulla

Group Art Unit: 1756

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT

SIR:

In response to the Office Action mailed on February 25, 2004, the period for responding thereto having been set to expire after May 25, 2004, please amend the subject application as follows: